

APAC SILICIDE 2016 PROGRAM

(updated 2016/6/15)

16th July

13:00—13:10 *Opening address*, Takashi Suemasu, Chairman APAC-SILICIDE 2016

Session I: Plenary

13:10—14:10 [16-PM-I-1] *Plenary*

Novel Growth-Techniques of Group-IV Based Semiconductors on Insulator for Post-Scaling Devices
Masanobu Miyao and Taizoh Sadoh
Department of Electronics, Kyushu University, Japan

14:10—14:40 [16-PM-I-2] *Invited*

Two-Dimensional Silicon Nanosheets; Controllable Exfoliation and Exploration of Functionality
Hideyuki Nakano
Toyota Central R&D Labs., Inc., Japan

Break 14:40—15:00

Session II: Silicide Basics

15:00—15:30 [16-PM-II-1] *Invited*

Structure and Electronic Properties of Low Dimensional Semiconducting Barium and Calcium Silicides
Dmitri B. Migas, Andrew B. Filonov, Vladislav O. Bogorodz, Victor E. Borisenko
Belarusian State University of Informatics and Radioelectronics, Belarus

15:30—15:50 [16-PM-II-2]

Electronic and Optical Properties of BaSi₂
Motoharu Imai, Mukesh Kumar and Naoto Umezawa
National Institute for Materials Science, Japan

15:50—16:10 [16-PM-II-3]

Synthesis of Crystalline Si-based Nanosheets by Extraction of Ca atoms from CaSi₂ in Inositol Hexakisphosphate (IP6) Solution
Xiang Meng¹, Kenta Sasaki², Koki Sano², Peiling, Yuan¹, Hirokazu Tatsuoka³
¹*Graduate School of Science and Technology, Shizuoka University, Japan*
²*Graduate School of Engineering, Shizuoka University, Japan*
³*Graduate School of Integrated Science and Technology, Shizuoka University, Japan*

16:10—16:30 [16-PM-II-4]

Low-Temperature Formation of Position-Controlled Large-Grain Ge on Insulator by Gold-Induced Crystallization Combined with Localized Nucleation
Taizoh Sadoh, Rikuta Aoki, Takahiro Tanaka, and Masanobu Miyao
Kyushu University, Department of Electronics, Japan

16:30—16:50 [16-PM-II-5]

Phase Composition Evolution of Iron Silicide Nanocrystallites in the Course of Embedding into Silicon

Evgeniy A. Chusovitin¹, Alexander V. Shevlyagin¹, Dmitry L. Goroshko^{1,2}, Sergey A. Dotsenko^{1,2}, Nikolay G. Galkin^{1,2} and Anton K. Gutakovskii³

¹ *Institute of Automation and Control Processes FEB RAS, Russia*

² *Far Eastern Federal University, Russia*

³ *Novosibirsk State University, Russia.*

17:00— 19:00 **Banquet**

17th July

Session III: Nano-Silicides & Silicide Spitronics

8:50— 9:20 [17-AM-III-1] *Invited*

Metal Silicide Nanowires for Detection and Manipulation of Magnetic Skyrmions

Matthew John Stolt and Song Jin

Department of Chemistry University of Wisconsin-Madison , USA

9:20— 9:40 [17-AM-III-2]

Spin Valve Junctions Comprising Fe-Si Materials

Tsuyoshi Yoshitake¹, Kazutoshi Nakashima¹, Kazuki Kudo¹, Kazuya Ishibashi¹, Yuki Asai¹, Ken-ichiro Sakai², and Hiroyuki Deguchi³

¹ *Department of Applied Science for Electronics and Materials, Kyushu University, Japan*

² *Dept. of Control and Information Sys. Eng., Nat. Inst. of Techn., Kurume Coll., Japan*

³ *Dept. of Basic Sci., Kyushu Inst. of Techn., Japan*

9:40— 10:00 [17-AM-III-3]

Formation of Fe₃Si-Nanodots on Ultrathin SiO₂ Induced by H₂-plasma Treatment and Their Magnetic-Field Dependent Electron Transport Properties

Hai Zhang, Katsunori Makihara, Mitsuhsa Ikeda, Akio Ohta and Seiichi Miyazaki

Graduate School of Engineering, Nagoya University, Japan

10:00—10:20 [17-AM-III-4]

Growth, Structure, Interfaces and Properties of Three-Layers Si(111)/[Fe-rich Silicide]/[Si-rich Silicide]/[Fe-rich Silicide]

A. Gournalnik¹, E. Pustovalov², Ko-Wei Lin³, A. Chuvilin^{4,5}, S. Chusovitina^{1,2}, S. Dotsenko¹, N. Galkin^{1,2}, A. Cherednichenko⁶ and V. Plotnikov²

¹ *Institute of Automation and Control Properties FEB RAS, Russia*

² *Far-Eastern Federal University, Physics Dpt., Russia*

³ *Department of Materials Sci. and Eng., National Chung Hsing University, Taiwan*

⁴ *CIC NanoGUNE Consolider, Tolosa Hiribidea , Spain*

⁵ *Ikerbasque, Basque Foundation for Science, Alameda Urquijo, Spain*

⁶ *Institute of Chemistry FEB RAS, Russia*

Break 10:20—10:40

Session IV: Silicide Green Technology; Thermoelectrics

10:40—11:10 [17-AM-IV-1] *Invited*

Recent Advances in Thermoelectric Silicides

Daryoosh Vashaee

Department of Electrical and Computer Engineering, Monteith Research Center, North Carolina State University, USA

11:10—11:30 [17-AM-IV-2]

The Enhancement of Power Factor of MnSi γ /AlMnSi Multilayer
Akinori Nishide, Yosuke Kurosaki, Shin Yabuuchi and Jun Hayakawa
Hitachi Ltd., R&D group, Center for exploratory Research, Japan

11:30—11:50 [17-AM-IV-3]

Influence of Mg-Related Defects on Structural and Electronic Properties of Mg₂Si
Naomi Hirayama, Iida Tsutomu, Keishi Nishio, Yasuo Kogo, Yoshifumi Takanashi, and
Noriaki Hamada
Tokyo University of Science, Japan

11:50—12:10 [17-AM-IV-4]

Preparation of Mg₂Si Thin Films on Various Kinds of Substrates and their Thermoelectric Properties
Mao Kurokawa¹, Mutsuo Uehara¹, Daichi Ichinose^{1,2}, Takao Shimizu³, Kensuke Akiyama^{1,4},
Masaaki Matsushima¹, Hiroshi Uchida⁵, Yoshisato Kimura², Hiroshi Funakubo^{1,2,3}
¹ *Department of Innovative and Engineered Materials, Tokyo Institute of Technology, Japan*
² *School of Materials and Chemical Technology, Tokyo Institute of Technology, Japan*
³ *Materials Research Center for Element Strategy, Tokyo Institute of Technology, Japan*
⁴ *Kanagawa Industrial Technology Center, Japan*
⁵ *Department of Materials and Life Science, Sophia University, Japan*

Lunch Break 12:10—13:30

Session V: Silicide Green Technology; Photovoltaics

13:30—14:00 [17-PM-V-1] *Invited*

Group IV Clathrates Developed for Photovoltaics
Tetsuji Kume¹, Fumitaka Ohashi¹, Kentaro Sakai², Atsuhiko Fukuyama³, Motoharu Imai⁴,
Haruhiko Udono⁵, Takayuki Ban¹, Hitoie Habuchi⁶, Hidetoshi Suzuki³, Tetsuo Ikari³, and
Shuichi Nonomura¹
¹ *Faculty of Engineering, Gifu University, Japan*
² *Center for Collaborative Research & Community Cooperation, University of Miyazaki, Japan*
³ *Faculty of Engineering, University of Miyazaki, Japan*
⁴ *National Institute for Materials Science, Japan*
⁵ *Graduate school of Science and Engineering, Ibaraki University, Japan*
⁶ *Department of Electrical and Computer Engineering, National Institute of Technology, Gifu College, Japan*

14:00—14:20 [17-PM-V-2]

Investigation of p-type Emitter Layer Materials for Heterojunction Barium Silicide Thin Film Solar Cells
Kazuma Takahashi¹, Yoshihiko Nakagawa¹, Kosuke O. Hara², Yasuyoshi Kurokawa¹,
Noritaka Usami¹
¹ *Graduate School of Engineering, University of Nagoya, Japan*
² *Center for Crystal Science and Technology, University of Yamanashi, Japan*

14:20—14:40 [17-PM-V-3]

Fabrication of B-doped p-BaSi₂ on n-Ge(111) Substrates for Heterojunction Solar Cells
Ryota Takabe, Suguru Yachi, Daichi Tsukahara, Kaoru Toko and Takashi Suemasu
Institute of Applied Physics, University of Tsukuba, Japan

14:40—15:00 [17-PM-V-4]

The Growth of Polycrystalline Orthorhombic BaSi₂ on Ge Substrate by Vacuum Evaporation Method

Cham Thi Trinh¹, Yoshihiko Nakagawa¹, Kosuke O. Hara², Ryota Takabe³, Takashi Suemasu³, and Noritaka Usami¹

¹ Graduate school of Engineering, Nagoya University, Japan

² Center for Crystal Science and Technology, University of Yamanashi, Japan

³ Institute of Applied Physics, University of Tsukuba, Japan

15:00—15:20 [17-PM-V-5]

Proposal of a Method to Realize BaSi₂ Thin Films with Uniform Orientation using Reactivity of Excessive Ba in the Film and Si Substrate in Vacuum Evaporation
Yoshihiko Nakagawa¹, Cham Thi Trinh¹, Kosuke O. Hara², Yasuyoshi Kurokawa¹, Takashi Suemasu³ and Noritaka Usami¹

¹ Graduate School of Engineering, Nagoya University, Japan

² Center for Crystal Science and Technology, University of Yamanashi, Japan

³ Institute of Applied Physics, University of Tsukuba, Japan

15:20—15:40 [17-PM-V-6]

Post -Annealing Effects on BaSi₂ Evaporated Films Grown on Si Substrates
Takamichi Suhara¹, Koichi Murata², Aryan Navabi², Kosuke O. Hara³, Yoshihiko Nakagawa¹, Trinh Cham Chi¹, Yasuyoshi Kurokawa¹, Takashi Suemasu⁴, Kang L. Wang², and Noritaka Usami¹

¹ Graduate School of Engineering, Nagoya University, Japan

² Department of Electrical Engineering, University of California, Los Angeles, USA

³ Center for Crystal Science and Technology, University of Yamanashi, Japan

⁴ Institute of Applied Physics, University of Tsukuba, Japan

Break 15:40—16:00

16:00—17:30 **Poster Session I**

17:30—19:00 **Poster Session II**

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Session VI: Thin film growth, Electric and Optical Properties, Silicide Devices

8:50— 9:20 [18-AM-VI-1] *Invited*

The Prospects for Silicon-Silicide Integrated Photonics

N.G. Galkin^{1,2}, A.V. Shevlyagin¹, D.L. Goroshko^{1,2}, E.A. Chusovitin¹, K.N. Galkin¹

¹ Institute of Automation and Control Processes, FEB RAS, Russia

² Far Eastern Federal University, School of Natural Sciences, Russia

9:20—9:40 [18-AM-VI-2]

Room-Temperature Luminescent Properties of the Si/ β -FeSi₂ Nanocrystals/Si LED

A.V. Shevlyagin¹, T.S. Shamirzaev^{2,3,4}, A.K. Gutakovskii^{2,3}, K.N. Galkin¹, E.A. Chusovitin¹, D.L. Goroshko^{1,5} and N.G. Galkin^{1,5}

¹ Institute of Automation and Control Processes FEB RAS, Russia

² Rzhanov Institute of Semiconductor Physics, SB RAS, Russia

³ Novosibirsk State University, Russia

⁴ Ural Federal University, Russia

⁵ Far Eastern Federal University, Russia

9:40—10:00 [18-AM-VI-3]

Analysis of Oxidation Behavior in Nanocrystal β -FeSi₂/Si Composites by Rutherford Backscattering Spectrometry and Computation of Diffusion Flux

Mikihiro Arima¹, Masaya Fuchi¹, Kazumasa Narumi², and Yoshihito Maeda^{1,2}

¹ *Department of Computer Science and Electronics, Kyushu Institute of Technology, Japan*

² *National Institutes for Quantum and Radiological Science and Technology(QST), Japan*

10:00— 10:20 [18-AM-VI-4]

Relaxation of Thermal Quenching of Photoluminescence from Nanocrystal β -FeSi₂/SiO₂ composites

Yoshihito Maeda

Department of Computer Science and Electronics, Kyushu Institute of Technology, Japan

Break 10:20—10:40

10:40—11:00 [18-AM-VI-5]

Optical Constants of Sputtered FeSi₂ Thin Films – Applications to Solar and Thermal Radiation Control

Motofumi Suzuki, Shoma Masunaka, Kensuke Nishiura and Kyoko Namura

Department of Micro Engineering, Kyoto University, Japan

11:00—11:20 [18-AM-VI-6]

Structural and electrical properties of β -FeSi₂ polycrystalline films with low electron density

Kazuya Ogi¹, Takahiko Higashi², Shuya Ikeda¹, Tetsu Hattori² and Yoshikazu Terai¹

¹ *Department of Computer Science and Electronics, Kyushu Institute of Technology, Japan*

² *Graduate School of Science and Engineering, Kagoshima University, Japan*

11:20— 11:40 [18-AM-VI-7]

Temperature-Dependent Magnetoresistance Effects in Fe₃Si/FeSi₂/Fe₃Si Trilayered Spin Valve Junctions

Kazuki Kudo¹, Kazuya Ishibashi¹, Kazutoshi Nakashima¹, Yuki Asai¹, Ken-ichiro Sakai², Hiroyuki Deguchi³, and Tsuyoshi Yoshitake¹

¹ *Department of Applied Science for Electronics and Materials, Kyushu University, Japan*

² *Department of Control and Information Systems Engineering, National Institute of Technology, Kurume College, Japan*

³ *Department of Basic Sciences, Kyushu Institute of Technology, Japan*

11:40—12:00 [18-AM-VI-8]

Impact of Mg₂Si Thin Film on Absorption and Efficiency of a-Si:H Based Solar Cells

I. M. Chernev¹, A. V. Shevlyagin¹, K. N. Galkin¹, J. Stuchlik², Z. Remes², T.H. Stuchlikova², R. Fajgar³ and N. G. Galkin^{1,4}

¹ *Institute of Automation and Control Processes of FEB RAS, Russia*

² *Institute of Physics of the ASCR, Czech Republic*

³ *Institute of Chemical Process Fundamentals of the ASCR, Czech Republic*

⁴ *School of Natural Sciences, Far Eastern Federal University, Russia*

12:15—12:30 **Closing and Ceremony**